

Users in the large-area and high-aspect-ratio coating industries will experience improved coating efficiencies when using Swing-DUO™ software.

When used with our exclusive Swing Cathode™, Swing-DUO™ (Dynamic Uniformity Optimization) software simulates the combined cathode array uniformity to produce individually optimized magnet bar motion profiles.

Features

- Dwell-based simulation finds the key deposition angles and calculates the amount of time required at each angle.
- Outputs a CAM table for simplified servo programming - angle and time format
- Optimizes uniformity for constant power or variable power
- Refines uniformity optimization using actual measured uniformity results
- Indicates the amount of wasted material not deposited on the substrate as a function of the motion profiles
- Web-based interface

Benefits

- Quickly designs coater configurations for optimal deposition uniformity
- Makes uniformity compensation for systemic issues in the form of motion profile changes
- Prevents uniformity drift over the life of the target by creating multiple CAM tables for different target diameters
- User friendly

A Swing-DUO™ Software demonstration is on the product page of the Sputtering Components website.

The software opens from the Sputtering Components website for registered users.

Simulated Four Cathode Swing Array

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Swing-DUO™ Software
Dynamic Uniformity Optimization

Optimization Results

±0.11% uniformity across the center region

3.74% of output deposited on neighbors

31.72% of output beyond the edge of the substrate

35.46% of output not deposited on the substrate

[Cathode Configuration](#)

[Simulation Output](#)

Magnet Bar Type	<input type="text" value="mQRM"/>	Target to Substrate Distance (TTS) (mm)	<input type="text" value="100.0"/>
Number of Angles	<input type="text" value="51"/>	Substrate Width (mm)	<input type="text" value="900.0"/>
Number of Cathodes	<input type="text" value="4"/>	Cathode Spacing (mm)	<input type="text" value="250.0"/>
Target Material OD (mm)	<input type="text" value="152.0"/>	<input type="button" value="Run Simulation"/>	